Claims as Amended

The Applicant hereby elects Group I device claims 1-16 with traverse.

The Applicant hereby withdraws Claims 17-20 for further consideration by the Examiner.

LISTING OF CLAIMS

- 1. (original) A particle-removing wafer, comprising:
 - a support body; and
- a particle-adherent layer having a particle-adherent surface carried by said support body.
- 2. (original) The particle-removing wafer of claim 1 wherein said support body comprises a silicon wafer.
- 3. (original) The particle-removing wafer of claim 1 wherein said particle-adherent layer comprises a plastic polytetrafluoroethylene film.
- 4. (original) The particle-removing wafer of claim 3 wherein said support body comprises a silicon wafer.
- 5. (original) The particle-removing wafer of claim 1 further comprising an adhesive layer provided between said support body and said particle-adherent layer.
- 6. (original) The particle-removing wafer of claim 5 wherein said support body comprises a silicon wafer.
- 7. (original) The particle-removing wafer of claim 5 wherein said particle-adherent layer comprises a plastic polytetra-fluoroethylene film.

- 8. (original) The particle-removing wafer of claim 7 wherein said support body comprises a silicon wafer.
 - 9. (original) A particle-removing wafer, comprising:
 - a support body;
 - a resilient layer carried by said support body:
 - an adhesive layer carried by said resilient layer; and
- a particle-adherent layer having a particle-adherent surface carried by said adhesive layer.
- 10. (original) The particle-removing wafer of claim 9 wherein said support body comprises a silicon wafer.
- 11. (original) The particle-removing wafer of claim 9 wherein said particle-adherent layer comprises a plastic polytetra-fluoroethylene film.
- 12. (original) The particle-removing wafer of claim 11 wherein said support body comprises a silicon wafer.
- 13. (original) The particle-removing wafer of claim 9 wherein said adhesive layer comprises a pair of adhesive surfaces.
- 14. (original) The particle-removing wafer of claim 13 wherein said support body comprises a silicon wafer.

15. (original) The particle-removing wafer of claim 13 wherein said particle-adherent layer comprises a plastic polytetra-fluoroethylene film.

16. (original) The particle-removing wafer of claim 15 wherein said support body comprises a silicon wafer.

17. (withdrawn) A method of removing particles from a surface, comprising the steps of: providing a particle-removing wafer having a particle-adherent surface; placing said particle-adherent surface into contact with the particles on the surface; and

removing said particle-removing wafer from the surface.

- 18. (withdrawn)The method of claim 17 wherein said particle-removing wafer comprises a support body and a particle-adherent layer carried by said support body, and wherein said particle-adherent surface is provided on said particle-adherent layer.
- 19. (withdrawn) The method of claim 18 wherein said support body comprises a silicon wafer.
- 20. (withdrawn) The method of claim 18 further comprising a resilient layer provided on said support body and an adhesive layer provided on said resilient layer, and wherein said particle-adherent layer is provided on said adhesive layer.